

ABSTRACT OF THE DISCLOSURE

Various inspection and review systems for wafers or reticles are provided. One system includes an optical component configured to project light onto a specimen during inspection or review. The system also includes a liquid disposed between and in contact with surfaces of the optical component and the specimen. The liquid does not permanently alter properties of the optical component or the specimen. Preferably, the presence of the liquid between the optical component and the specimen increases the resolution of the inspection or review system. Another system includes an inspection or review subsystem configured to project light through an optical component, a liquid, and onto a specimen. The liquid contacts the optical component and the specimen. This system also includes a processing subsystem configured to remove the liquid from the specimen after inspection or review. In some embodiments, the processing subsystem is configured to clean the specimen after inspection or review.

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